

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	22	257/E21.023.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/06 09:27
L2	486	257/E21.035.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/06 10:09
L3	19	(photoresist or resist) near3 (viscosity or viscous) near8 (smooth or smoothness or rough or roughened or roughness or crack or cracking or void)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/06 10:10
S23	16	(US-20010027013-\$ or US-20030165770-\$ or US-20040137707-\$ or US-20050277245-\$).did. or (US-6893791-\$ or US-6852465-\$ or US-6524774-\$ or US-6335216-\$ or US-6218281-\$ or US-5108950-\$ or US-6784089-\$ or US-6649507-\$ or US-6602775-\$ or US-6372622-\$ or US-6515233-\$ or US-6331449-\$).did.	US-PGPUB; USPAT	OR	ON	2006/10/30 09:43
S24	362	(bond near pads or bonding near pads or electrodes or terminals) near3 (solder or ball or bump or bumping) same (plural or plurality or multiple or multi or laminated or laminate or stack or stacked or stacking or second or secondary or top or upper) near3 (photoresist or photo-resist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 09:48
S25	20	(bond or bonding or pads or electrodes or terminals or ubm) near3 (solder or ball or bump or bumping) and (plural or plurality or multiple or multi or laminated or laminate or stack or stacked or stacking or second or secondary or dual or double or layered) near3 (photoresist or photo-resist or resist) same (viscous or viscosity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 10:47

EAST Search History

S26	91	(bond or bonding or pads or electrodes or terminals or ubm) near3 (solder or ball or bump or bumping) same ((plural or plurality or multiple or multi or second or secondary or dual or double) near layer\$2) near3 (photoresist or photo-resist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 10:59
S27	89	(bond or bonding or pads or electrodes or terminals or ubm) near3 (solder or ball or bump or bumping) same (photoresist or photo-resist or resist) and (photoresist or photo-resist or resist) near4 (viscosity or viscous or fluidity or fluid or liquidity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 11:18
S28	206	(photoresist or photo-resist) near5 (viscosity or viscous) near6 (thick or thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 11:58
S29	228	438/671.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 12:15
S30	517	(438/612,613,614,669,671,675.ccls.) and ((plural or plurality or multi or multiple or dual or two or second or secondary) near2 (layer or layered) or multilayered or multilayer or laminat\$5 or stack or stacked) near2 (resist or photoresist or photo-resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 12:36
S31	798	438/675.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/30 13:19
S32	13	"6602775".pn. "20050277245" "6649507".pn. "6372622".pn. "20030165770" "6335216".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/03 15:35
S33	554	(planarization or polymer or oxide) near5 (adhesion or adhering) near4 (photoresist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/03 16:27
S34	50	(photoresist or resist) near8 (adhesion or adhering) near10 (viscosity or fluidity or viscous)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/03 16:30

EAST Search History

S35	2	(metal or solder or contact or electrode) near5 (bridging or shorting) same (resist or photoresist) near4 (viscous or viscosity or fluidity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/03 16:31
S36	687	(multilayer or (multi or multiple or plural or dual or plurality or second) near2 (layer)) near2 (photoresist or resist) and (photoresist or resist) near3 (viscosity or viscous or fluidity or adhesion)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/03 16:36
S37	237	(multilayer or (multi or multiple or plural or dual or plurality or second) near2 (layer)) near2 (photoresist or resist) and (photoresist or resist) near3 (viscosity or viscous or fluidity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/11/06 09:12